

## Material and processing science in nanoimprint lithography

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Our group has dedicated to pursue scientific principles for molecular control of interface function occurring at polymer/other material interfaces and to put them into practice in nanoimprint lithography promising as a next generation nanofabrication tool. We are developing advanced photo-functional materials such as sticking molecular layers for "fix by light", UV-curable resins and antisticking molecular layers for "preparation by light", fluorescent resist materials for "inspection by light", and hybrid optical materials "available to light" and new research tools such as mechanical measurement systems to evaluate release property of UV-curable resins. Our research aims at creating new devices to control photon and electron.

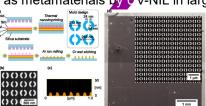


screen printing system





Formation of nanosized metal structures as metamaterials by UV-NIL in large area



Appl. Phys. Lett., 2013, 103, 071104 (1-4).

laser drilling system

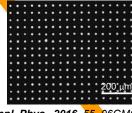


## laser drilling

Preparation of polymer through-hole membranes by pulsed laser drilling

laser materials processing



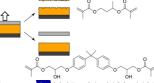


Jpn. J. Appl. Phys., 2016, 55, 06GM01. Position selective placement of resin dots with controlled volume by screen printing process

Low pollution of fluorinated mold surfaces in UV-NIL

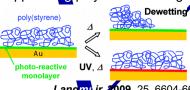
demolding

etching.



Langmuir, 2015, , 31, 4188–4195.

Formation of a photoreactive chemisorbed monolayer for suppressing polymer dewetting

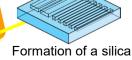


Langmi ir, 2009, 25, 6604-6606.

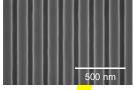
nanoimprint lithography

@ Nakagawa lab.





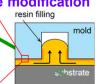
template by electron beam lithography

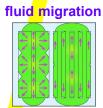


## resin filling

surface modification



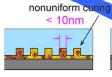




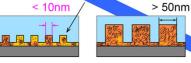
**UV** nanoimprinting system



uniform curing of a photo-curable resin during UV nanoimprinting in single-nanometer regime



**UV** curing

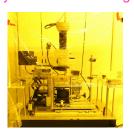


Bubble-defect free UV nanoimprinting

under condensable gas atmosphere

Microelectron. Eng., 2015, 133, 134-155.

real-time observation system for resin filling



development of UV-curable resin